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NMR spectra of a few 4-substituted 1,2-bis(trimethylsiloxy)benzenes and positional isomers of bis(trimethylsiloxy)benzene were measured under standard conditions that approach those of infinite dilution. Under these conditions somewhat smaller values of steric or proximity deshielding effects on 29 Si chemical shifts are found but the trends established earlier are confirmed; the deshielding effect of the "second" *ortho* positioned trimethylsiloxy group in a tris-(trimethylsiloxy)benzene derivative on 29 Si chemical shift is somewhat smaller. Also, over-crowding of three trimethylsiloxy groups probably drives the outer groups to assume, at least for a part of their time, coplanar conformation which is not encountered in bis(trimethylsiloxy)-derivatives. The sensitivity of 29 Si chemical shifts to *para* substitution is in 1,2-bis(trimethylsiloxy)benzenes equal to that in 2-methoxytrimethylsiloxybenzenes.

In connection with our studies of *ortho* substituted trimethylsiloxybenzenes¹ we have investigated a series of 4-substituted 2-methoxytrimethylsiloxybenzenes² which model structures encountered in important applications of ²⁹Si NMR to analysis of lignins³⁻⁵. The results of these studies lead to the conclusion that the trimethyl-siloxy (TMSO) group is for most of its time in a conformation in which the O—Si bond is perpendicular to the benzene ring plane and the *ortho* positioned methoxy group is in a coplanar conformation with the methyl group turned away from the TMSO group. These findings were later confirmed in a study of 2,6-dimethoxytrimethylsiloxybenzenes⁶ in which the two *ortho* positioned methoxy groups do not allow the TMSO group to assume coplanar conformation. Proximity deshiedling effects that were observed both in ²⁹Si and ¹³C NMR spectra of these compounds could be explained by an interaction of the oxygen atom of the TMSO group with the unshared electrons of the *ortho* substituent(s).

Since this conformational behavior of TMSO groups on benzene ring is so markedly different from that of methoxy groups deduced by the same means⁷⁻¹¹ from the ¹³C NMR spectra of methoxybenzenes, we have undertaken the present limited study of several derivatives of bis(trimethylsiloxy)benzenes with the aim to establish whether the TMSO groups behave in these compounds as they do in mono

trimethylsiloxybenzenes or whether they behave more like the methoxy groups in polymethoxybenzenes $^{7-11}$.

EXPERIMENTAL

The parent compounds for trimethylsilylation were of commercial origin except for 1,2-dihydroxy--4-methylbenzene and 3,4-dihydroxyacetophenon. The former compound was prepared from vanilin in two steps. Thus, vanilin was demethylated by aluminium chloride in dichloromethane¹² to yield 3,4-dihydroxybenzaldehyde, which was then reduced by catalytic hydrogenation in methanol over palladium on charcoal by a standard procedure. 3,4-Dihydroxyacetophenon was prepared by reaction of 1,2-dihydroxybenzene with acetic acid in polyphosphoric acid in a way described by Nakazawa¹³. Trimethylsilylation, product purification and spectral measurements were carried out exactly as described previously². For convenience the most significant features of NMR measurements are brieffy repeated here: the samples were dissolved in deuteriochloroform containing 2% of hexamethyldisilane (HMDSS). The ¹³C NMR spectra were referenced to the central line of the solvent ($\delta = 76.99$) and the samples were diluted by this solvent until ¹³C chemical shift of HMDSS reached the value $\delta = -2.48 \pm 0.02$. The ²⁹Si NMR spectra were referenced to the line of HMDSS ($\delta = -19.79$).

The chemical shifts of the aromatic carbons were also calculated according to the direct additivity rule using the substituent-induced chemical shift (SCS) values derived for the TMSO group earlier² and the SCS values of the other substituents measured under comparable conditions¹⁴.

RESULTS AND DISCUSSION

Table I summarizes the experimental results for compounds I - VIII.



The NMR based arguments for coplanar conformation of methoxy groups in methoxybenzenes rest essentially on systematic and consistent deviations, Δ , of experi-

Substituted Bis(trimethylsiloxy)benzenes

TABLE I

²⁹Si and ¹³C NMR chemical shifts^{*a*} in compounds I - VIII

Compound	²⁹ Si	¹³ C						
		C-1	C-2	C-3	C-4	C-5	C-6	MeSi
I	19.29	155.16	120.07	129.39	121.41	129.39	120.07	0.17
II	20.26	146·58 (−0·34	146·58 —0·34	$121 \cdot 11^{b}$ -0.04	121·80 ^b 0·69	121·80 ^b — 0·69	121·11 ^b −0·04)	0.32
III	19.50	156.12	112-25	156.12	113-46	135-43	11 3·4 6	0·19
IV	19.12	149.39	120.53	120.53	149.39	120.53	120.53	0.12
V	19·94 ^c	144·13 (0·26	146·13 0·70	121·86 0·02	131·34 −0·73	122·21 — 0·97	120·67 —0·39)	0·34 ^c
VI	21·69 ^d	151·25 (−0·09	146·29 0·54	122·70 0·38	123·94 ^e —0·69	124·57 0·91	120·34 — 0·72)	0·30 ^f
VII	21·91 ^g	151·52 (−0·07	146·56 —0·27	120·83 ^b 0·47	131·54 0·36	123·24 ^b 0·60	120·32 ^b 0·74)	0·30 ^c
VIII	22·45 ^f	143·48 (0·47	147·55 0·18	115·75 —0·05	$123.69 - 1.33^{e}$	115·75 —0·58	147·55 0·36) ^j	0.64 <i>°</i>

^a Chemical shifts in δ – scale, approximate error ± 0.02 ppm. Lines in parentheses give deviations, Δ , of experimental values δ_{exp} from the shifts calculated according to the additivity rule, $\Delta = \delta_{exp} - \delta_{calc}$. ^b Assignments in the row can be interchanged. ^c Accidentally single line. ^d Other lines δ (Si-2) = 21.32 and δ (SiOOC) = 24.06, assigned according to ref.¹⁵. ^e Possibly in error due to an impurity. ^f Other line with lower intensity at $\delta = -0.15$ is due to ester group, ref.¹⁵. ^g Assignment uncertain, the other line at $\delta = 21.53$. ^h Other lines at δ (Si-2,6) = 21.25 and δ (SiOOC) = 23.97 assigned according to ref.¹⁵. ⁱ Other lines at $\delta = 0.26(2)$ and -0.21. ^j The values of δ_{calc} used for evaluation Δ were calculated from the chemical shifts in the compound VI and SCS values of TMSO group.



FIG. 1

Correlation of $\delta(^{29}Si)$ in 4-substituted 2,3--bis(trimethylsiloxy)benzenes vs $\delta(^{29}Si)$ in 4--substituted 1-methoxytrimethylsiloxybenzenes²

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mental aromatic carbon chemical shifts from the shifts predicted according to the direct additivity of substituent effects. Chemical shifts of aromatic *ortho* carbons *cis* to the methyl group are smaller and those that are *trans* (refs⁷⁻¹¹) are larger than the calculated values. In the derivatives with two *ortho* positioned trimethylsiloxy groups (i.e. in compounds *II*, *V*, *VI* and *VII*) we do not find such trends for C-1 and C-3 aromatic carbons (i.e. positive Δ for C-1 and negative for C-3). However, deviations found for carbons C-1 and C-5 which are *ortho* to TMSO group in the compound *VIII* have such signs. Perhaps, overcrowding in this compound turns the two outer TMSO groups toward the benzene plane.

The proximity deshielding effects on ²⁹Si and ¹³C chemical shifts of TMSO group in benzene derivatives were first reported for *ortho* substitution by TMSO group¹⁶; later, this effect was found¹ to be a general feature of *ortho* substituents containing unshared electrons. The reported values^{1,16} were, however, obtained from concentrated solutions. The present data, which approximate infinite dilution shifts in deuteriochloroform, yield values of the proximity deshielding effects of TMSO group that are for ²⁹Si chemical shifts somewhat smaller (1·1 ppm, as the average of the difference between the shifts in *II* and *IV* and in *II* and *I*) and for ¹³C chemical shift essentially the same (0·16 ppm) as the values found in the concentrated solutions¹⁶ for this group. Analogous comparison of the chemical shifts in compounds *VIII* and *VI* provides estimates of the proximity effects of the "second" ortho TMSO group. The effects are also deshielding (0·8 and 0·3 ppm for ²⁹Si and ¹³C chemical shifts, respectively) but according to their relative magnitude we cannot exclude the possibility of a contribution from an interaction of terminal methyl groups that was not observed in mono ortho substituted trimethylsiloxybenzenes^{1,2,16}.

Though the available data are limited, it is apparent from Fig. 1 that the ²⁹Si chemical shifts in 4-substituted 1,2-bis(trimethylsiloxy)benzenes and in the corresponding 2-methoxytrimethylsiloxybenzenes exhibit approximately the same sensitivity to substitution.

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